

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: Davis, et al.	§	Case: AMAT/7938/ETCH/SILICON/JB
	§	
Serial No.: 10/628,001	§	Filed: July 25, 2003
	§	
Examiner: Stevenson, Andre C.	§	Group Art Unit: 2812
	§	
Confirmation No.: 3943	§	
	§	
Title: METHOD FOR AUTOMATIC	§	
DETERMINATION OF	§	
SEMICONDUCTOR PLASMA	§	
CHAMBER MATCHING AND	§	
SOURCE OF FAULT BY	§	
COMPREHENSIVE PLASMA	§	
MONITORING	§	

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 Commissioner for Patents
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S I R:

RESPONSE TO FINAL OFFICE ACTION DATED FEBRUARY 10, 2006

In response to the Final Office Action dated February 10, 2006, having a shortened statutory period for response set to expire on May 10, 2006, and the Advisory Action dated June 26, 2006, please enter this response and reconsider the claims pending in the application for reasons discussed below. The Applicants have submitted payment for a one-month extension to reply using the Patent Electronic Business Center. Although Applicants believe that no other fees are due in connection with this response, the Commissioner is hereby authorized to charge counsel's Deposit Account No. 20-0782 for any fees, including additional extension of time fees, required to make this response timely and acceptable to the Office.